Supporting Information

Surface Composition, Chemistry, and Structure of Polystyrene Modified by Electron-Beam-Generated Plasma

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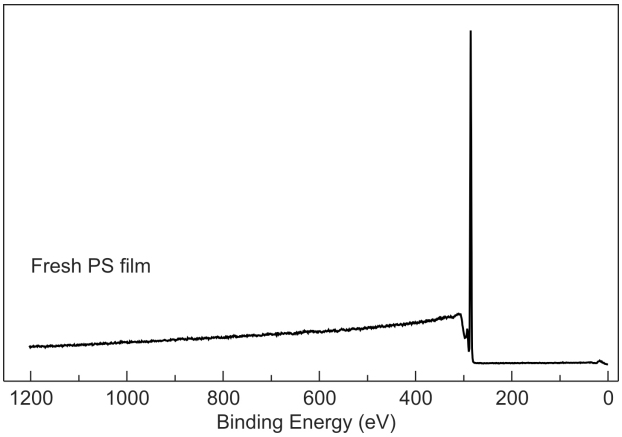

Figure SI1. XPS survey of a freshly spin-cast polystyrene film.

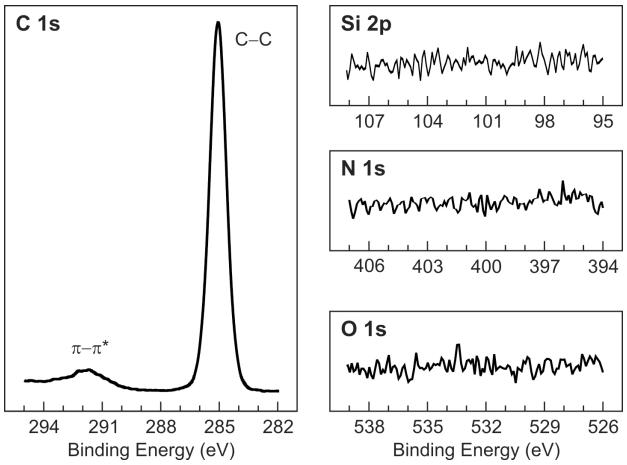

Figure SI2. High-resolution XPS data for a freshly spin-cast polystyrene film. Note that any O, N, or Si impurities or contaminants are below XPS detection limit for these PS films.

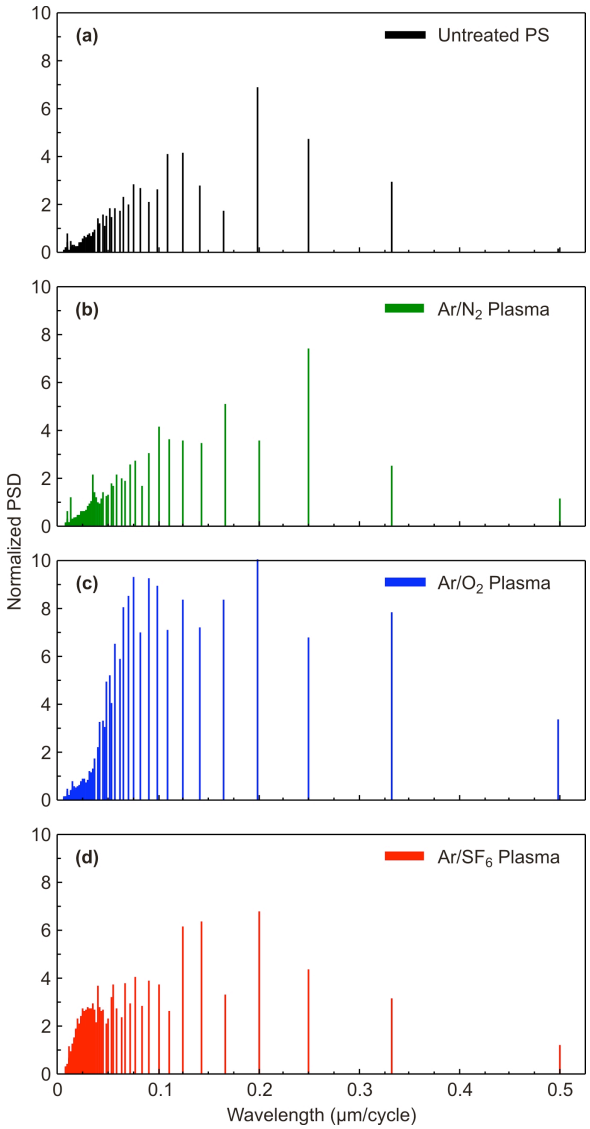

Figure SI3. Power spectra of surface roughness for plasma-treated polystyrene films. PSD profiles were calculated from AFM data (Figure 1) for PS surfaces treated in Ar/N_2 (b), Ar/O_2 (c), and Ar/SF_6 (d) plasma environments. Panel (a) shows a reference PSD for untreated PS sample.

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